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**CMR INSTITUTE OF TECHNOLOGY**

Internal Assessment Test – I											
Sub:	VLSI DESIGN						Code:	18EC72			
Date:	30.10.2023	Duration:	90 mins	Max Marks:	50	Sem	VII	Branch	ECE-A,B,C,D		
Answer Any Five Questions											
Questions							Marks	OBE			
								CO	RIT		
1.	Explain the operation of an n-channel enhancement mode MOSFET with neat diagrams.						[10]	CO1	L1		
2.	Derive the expression for Drain to source current for an n-channel MOSFET in all three regions.						[10]	CO1	L2		
3.	Describe in detail about any five non-ideal I-V characteristics of MOS transistor.						[10]	CO1	L1		

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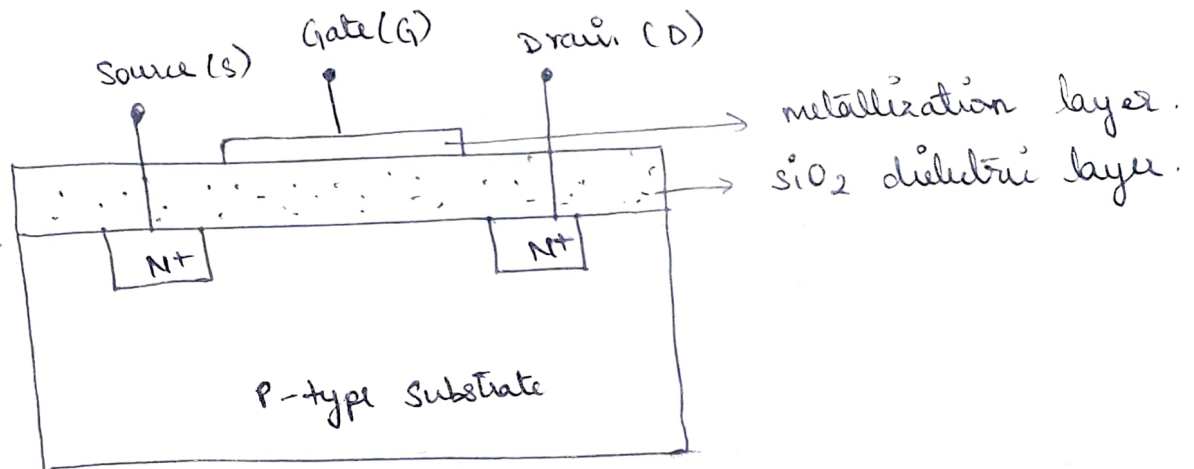
4.	Realize the following logic expression using CMOS: a) $Y = \overline{(A.B) + (C.D)}$ b) $Y = \overline{A + BC}$	[10]	CO1	L2
5.	Illustrate with neat sketch, explain the DC transfer characteristics of CMOS inverter.	[10]	CO1	L2
6.	With necessary circuit diagram, explain the operation of transmission gate. Also realize a 4:1 multiplexer using transmission gate.	[10]	CO1	L3

CI

CCI

HOD

Q1) Basic structure of n-channel enhancement mode MOSFET is shown below.



→ When the gate voltage is zero ( $V_g = 0$ ) and no positive voltage is applied across between the source and drain ( $V_{ds}$ ), the PN-junction is reverse-biased.

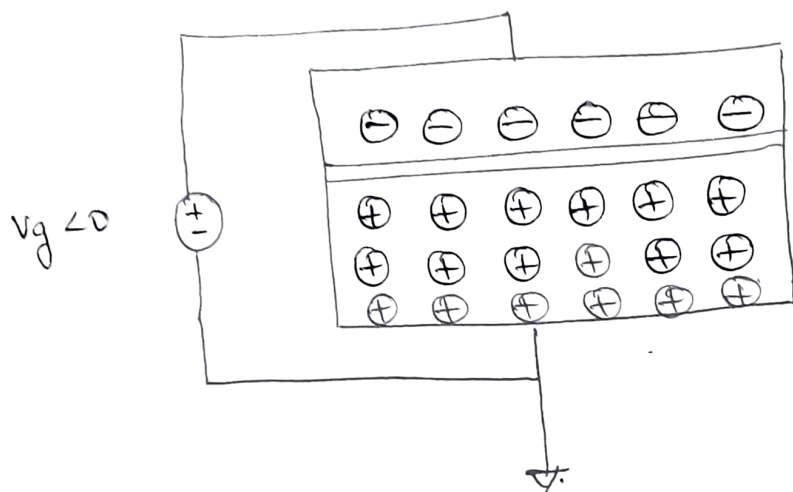
→ Since there is no current flow across the substrate and region below the gate, MOSFET is in OFF condition.

→ When a positive voltage is applied to the gate i.e. when the gate to source voltage increases, it induces an electric field  $E$  across the substrate which attracts electrons and repels holes.

→ At this condition, when the gate voltage is increased further, the gate of p-type changes to n-type.

→ Based on applied voltage, there are 3 modes of operation.

(i) Accumulation Mode:



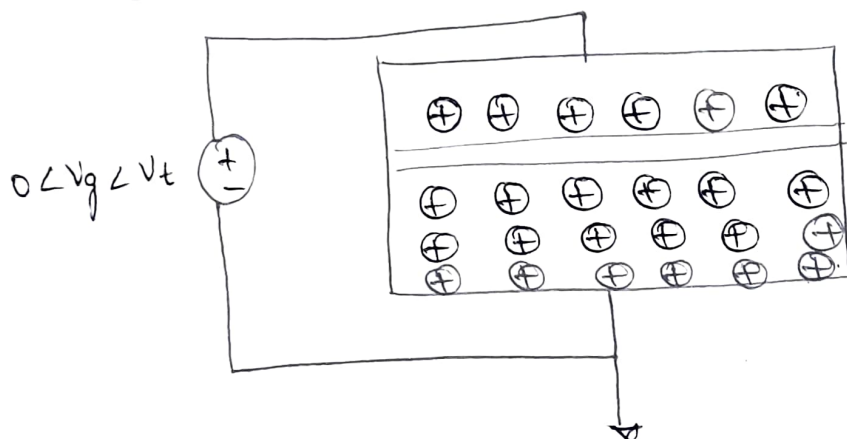
→ When the gate voltage is equal to 0 ( $V_g = 0$ ) or voltage less than 0 is applied to the gate (-ve voltage), electrons get accumulated at the region below the gate.

→ This mode is known as accumulation mode.

→ There is no conduction between the drain & source.

→ The device is in OFF condition.

(ii) Depletion mode.



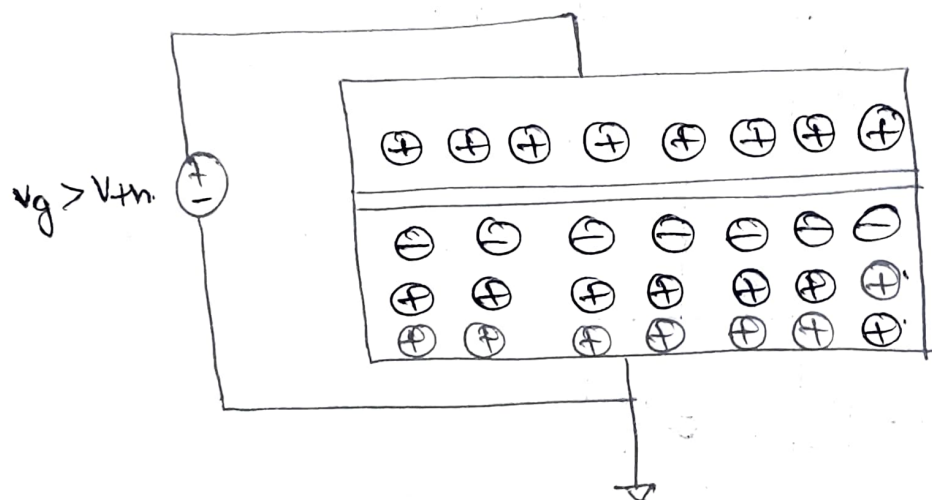
→ When voltage greater than 0 but less than threshold voltage is applied to the gate, it is known as depletion mode.

→ The electrons get attracted towards the gate and holes are repelled towards the region under gate.

→ This creates a depletion layer in the region below the gate and hence is known as depletion mode.

iii) Inversion Mode.

Condition



Cut off  
Linear  
Saturation

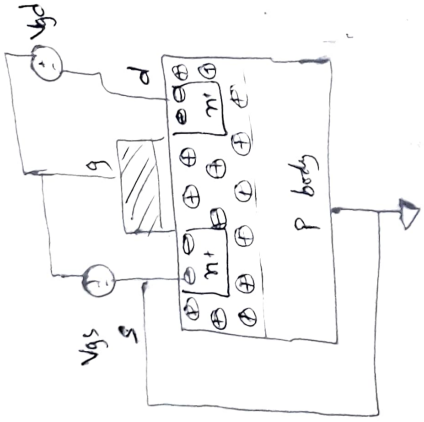
→ When the positive voltage is increased further i.e. when the gate voltage is raised above threshold voltage, the electrons are attracted towards the substrate.

→ The holes are repelled towards the gate.

→ At this stage, on increasing the voltage p-type changes to n-type.

→ Conduction takes place in this mode.

→ Since electrons are attracted towards substrate & holes are repelled towards gate, an inversion layer is created.



→  $V_{gs} < V_t$

→ Transistor is in off state.

→ The junction between drain and source is  $\ominus$  or reverse biased

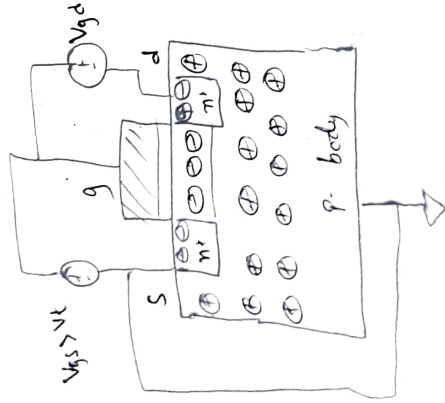
thus no current flows

→  $I_{ds} = 0$

→ It is called cut off region.

→ Also there is no channel formed.

→ Source is grounded.



→  $V_{gs} > V_t$

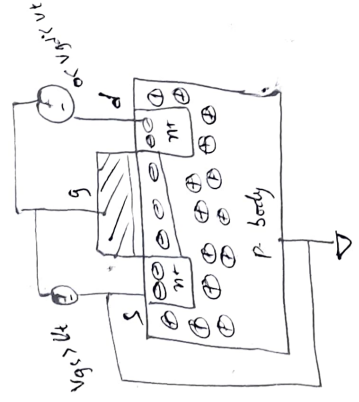
→  $V_{gs} = V_{gd}$

→ The channel layer

is formed b/w drain and source. called inversion layer below the gate.

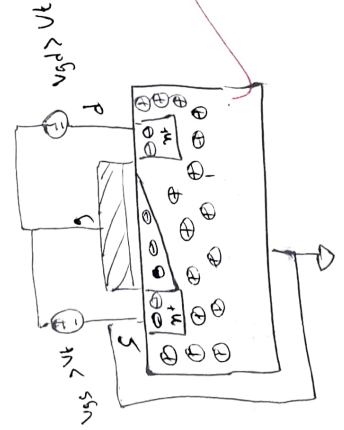
→  $V_{ds} = 0$

iii) Linear Region.



- $V_{gs} > V_t$
- $V_{ds} = V_{gs} - V_{gd}$
- As  $V_{ds} = 0$
- $V_{gs} = V_{gd}$
- The E-field push Ids from drain to source.
- This forms a channel b/w source and drain called linear region.

iv) Saturation Region



- $V_{gs} > V_t$
- $V_{gd} > V_t$  (Saturation)
- $\Delta \text{Len } V_{out} > V_{gs} - V_t$
- it forms saturation region, where the layer gets pinched off towards the source.

→ Some positive drain voltage is still present that cause  $e^-$  to flow.

Ans 2.1)

In cut off region  $V_{GS} < V_t$

There is no current flowing  $\therefore I_{DS} = 0$ .  
Out off.

$$Q = CV \quad \text{--- (1)}$$

$$C = C_g = C_{ox} WL \quad \text{--- (2) (Total capacitance)} \quad C_{ox} = \frac{\epsilon_{ox}}{t_{ox}}$$

$$V = V_g - V_t \quad \text{--- (3)}$$

$$V_g = \frac{V_{GS} + V_{GD}}{2} \quad \text{--- (4)}$$

$$V_{DS} = V_{GS} - V_{GD} \quad \text{--- (5)}$$

$$\therefore V_{GD} = V_{GS} - V_{DS} \quad \text{--- (6)}$$

Putting (6) in (4)

$$V_g = \frac{2V_{GS} - V_{DS}}{2} \quad \rightarrow V_g = V_{GS} - \frac{V_{DS}}{2} \quad \text{--- (7)}$$

$$\text{Also } V = V_{GS} - \frac{V_{DS}}{2} - V_t \quad \text{--- (8)}$$

$$V = \mu E \quad (\text{Charge Velocity}) \quad t = \frac{L}{V} = \frac{L}{\mu E}$$

$$Q = \frac{Q}{t} \quad \checkmark \quad E = \frac{V_{DS}}{L}$$

$$I_{DS} = \frac{C_g V}{t}$$

$$I_{DS} = \frac{C_{OX} \mu_n E}{L} \left( V_{GS} - \frac{V_{DS}}{2} - V_T \right)$$

$$= C_{OX} \mu_n E \left( V_{GS} - \frac{V_{DS}}{2} - V_T \right)$$

$$= C_{OX} \mu_n \frac{V_{DS}}{L} \left( V_{GS} - \frac{V_{DS}}{2} - V_T \right) \quad \left[ \because E = \frac{V_{DS}}{L} \right]$$

$$I_{DS} = C_{OX} \mu_n \frac{V_{DS}}{L} \left( V_{GS} - \frac{V_{DS}}{2} - V_T \right) \quad \rightarrow \text{Linear Region.}$$

for Saturation region  $V_{DS} = V_{GS} - V_T$

$$\therefore I_{DS \text{ sat}} = \beta V_{DS} \left( V_{GS} - \frac{V_{DS}}{2} - V_T \right)$$

$$= \beta \left( V_{GS} - V_T \right) \left( V_{GS} - V_T - \frac{V_{GS} - V_T}{2} \right)$$

$$I_{DS} = \frac{\beta}{2} \left( V_{GS} - V_T \right)^2 \quad \rightarrow \text{Saturation region.}$$

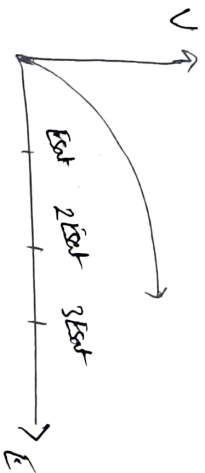
$$\beta = \frac{C_{OX} \mu_n}{L}$$



## i) Charge mobility

$$V = \mu \vec{E}$$

- $\mu$  is a constant term.
- If  $\vec{E}$  increases, then  $\mu$  also increases which in turn increases the electron mobility that is ' $V$ ' at  $\vec{E}_{sat}$ .



- If  $V$  is not saturated

$$I_{ds} = \frac{\mu C_{ox} W L}{2} (V_{GS} - V_T)^2$$

- If ' $V$ ' is saturated

$$I_{ds} = \mu C_{ox} W (V_{GS} - V_T) V_{DS}$$

- From above eqn it can be seen that if  $V$  is saturated it is quadratically dependent and for saturation it is linearly dependent.

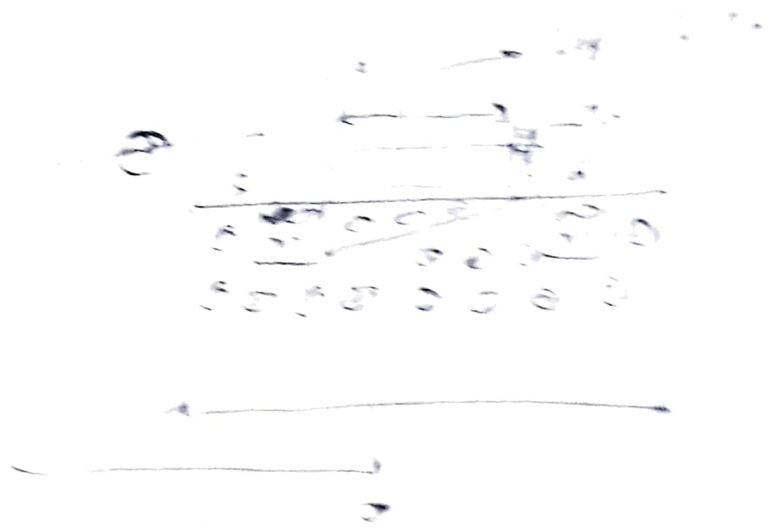


### Mobile to Segregation

- As  $V_{max}$  &  $K_m$  are change means in the direction of length of separation it get attached to the surface that is the mobility.
- If mobility is decreased the job also get reduced that is called mobile to segregation.

### Channel length modulation

- It is a form of VLSI but if the channel length is beyond  $1 \mu m$  the job is also affected.
- This reduce the channel length due to the reduction in the carrier velocity.
- This is called as channel length modulation.
- This is off = ...



→ ... ..

## v) Body Effect

→ When potential between body and source is reduced it also affects the  $V_t$ .

→ Thus when  $V_t$  is also reduced it is called body effect.

→ Transistor has 4<sup>th</sup> implicit terminal called body.

$$V_t = V_{t0} + \gamma \left( \sqrt{\phi_s - V_{SB}} - \sqrt{\phi_s} \right)$$

→ This equation gives the  $V_t$  dependence on  $\gamma$

$\gamma$  → Body pot. Coefficient.

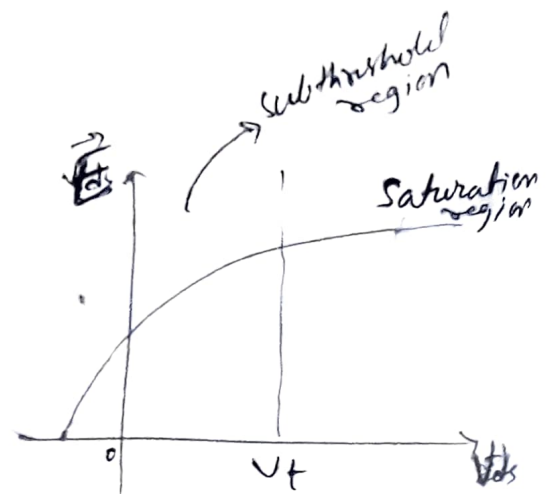
$V_{t0}$  → pot when  $V_t$  is at saturation

$\phi_s$  → pot when body saturation.

## v) Junction Leakage

→ It is the leakage current when there is saturation.

## vi) Sub-threshold region

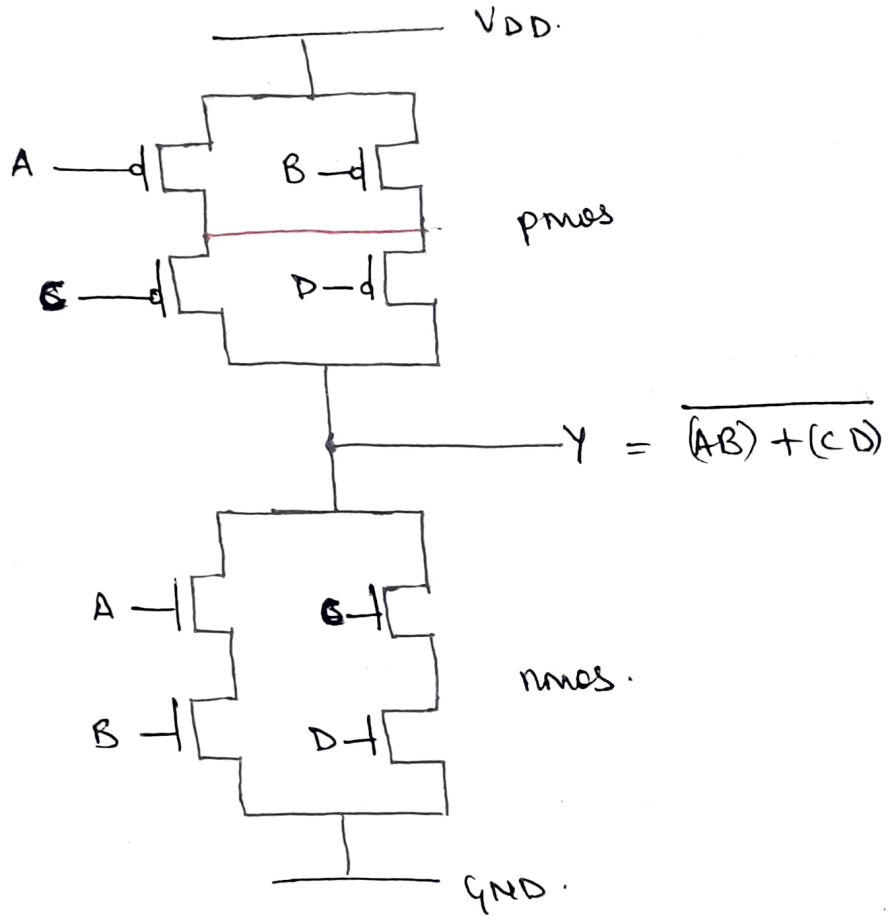


84)

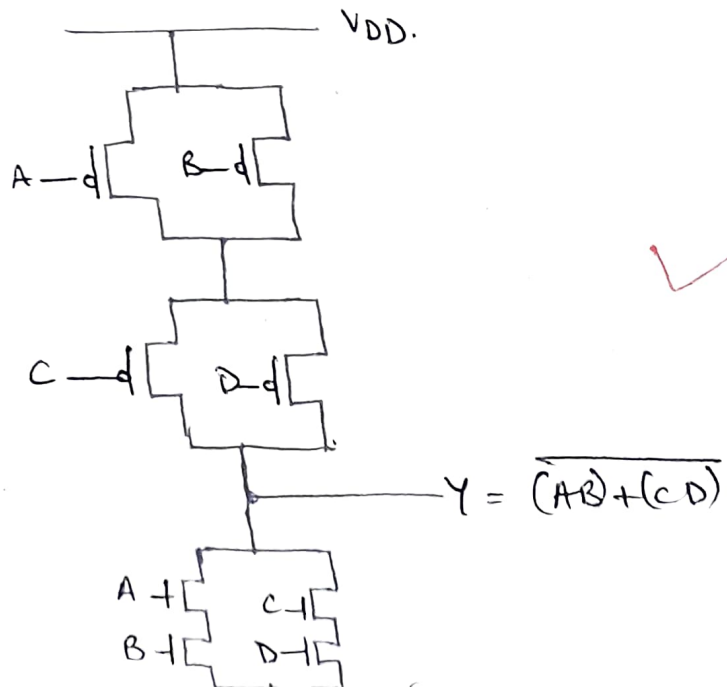
(a)  $Y = \overline{(AB) + (CD)}$

nmos  
and - series  
or - parallel

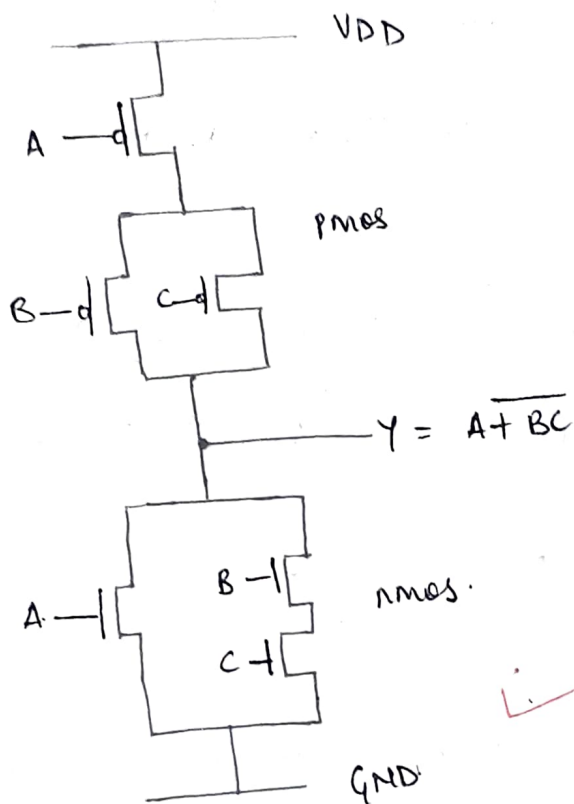
pmos  
and - parallel  
or - series



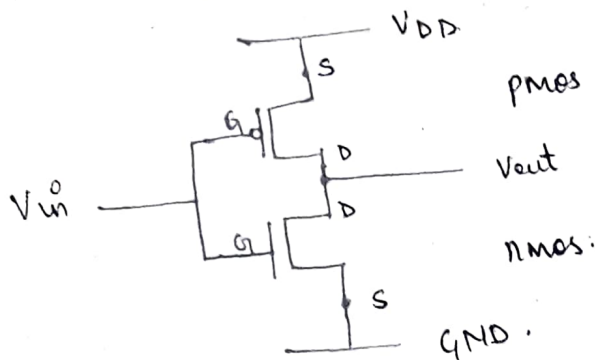
or



(b)  $Y = \overline{A + BC}$



Q5)  $\Rightarrow$  DC transfer characteristics of CMOS inverter relates to the output voltage to the input voltage.



CMOS structure

- $\Rightarrow$  The threshold voltage of pmos ( $V_{tp}$ ) is always negative.
- $\Rightarrow$  The threshold voltage of nmos ( $V_{tn}$ ) is always positive.

For nmos:

$$V_{gsn} = (V_g - V_s)_n = V_{in} - 0 = \underline{V_{in}}$$

$$V_{dsn} = (V_d - V_s)_n = V_{out} - 0 = \underline{V_{out}}$$

For pmos:

$$V_{gsp} = (V_g - V_s)_p = V_{in} - \underline{V_{DD}}$$

$$V_{dsp} = (V_d - V_s)_p = V_{out} - \underline{V_{DD}}$$

\* Regions of operation for pmos and nmos:

for nmos:

$V_{gsn} < V_{tn} \rightarrow$  cut-off region

$V_{gsn} > V_{tn} \rightarrow$  either saturation or linear

$\rightarrow V_{dsn} < V_{gsn} - V_{tn} \rightarrow$  linear region

$\rightarrow V_{dsn} \geq V_{gsn} - V_{tn} \rightarrow$  saturation region

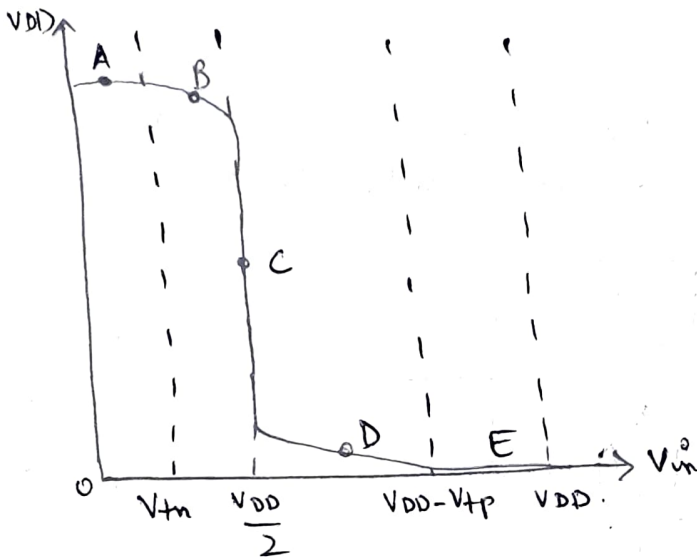
for pmos:

$V_{gsp} > V_{tp} \rightarrow$  cut-off region

$V_{gsp} < V_{tp} \rightarrow$  either saturation or cut-off

$\rightarrow V_{dsp} > V_{gsp} - V_{tp} \rightarrow$  linear region

$\rightarrow V_{dsp} \leq V_{gsp} - V_{tp} \rightarrow$  saturation region



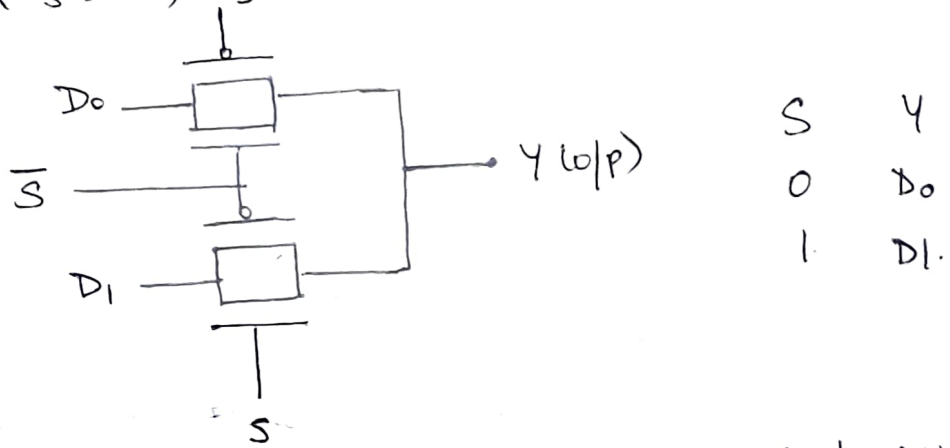
Region	nmos	pmos
A	cut-off	linear
B	saturation	linear
C	saturation	saturation
D	linear	saturation
E	linear	cut-off

- In region A: pmos transistor is on and pulls the o/p to VDD  
nmos transistor is OFF. (cut-off region)
- In region B: nmos transistor starts to turn ON, pulling the output down. (saturation region).
- In region C: Both the transistors are in saturation region.
- In region D: The pmos transistor is partially ON.
- In region E: pmos transistor is OFF. Hence the nmos transistor drives / pulls the output down to 0.

8b)

### Transmission gate

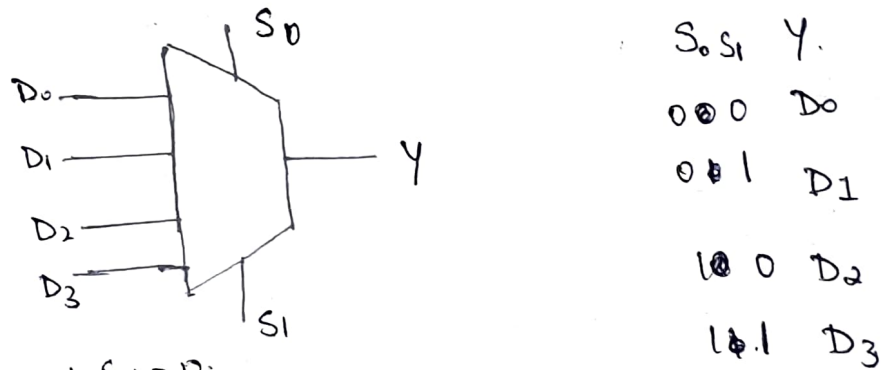
In this example, selection line  $S=0$  selects  $D_0$  as the o/p. and when  $S=1$ ,  $S$  it selects  $D_1$  as the i/o/p.



This a transmission gate for a 2:1 MUX.

### Incase of 4:1 MUX :

→ There are 4 inputs and 2 selection lines with 1



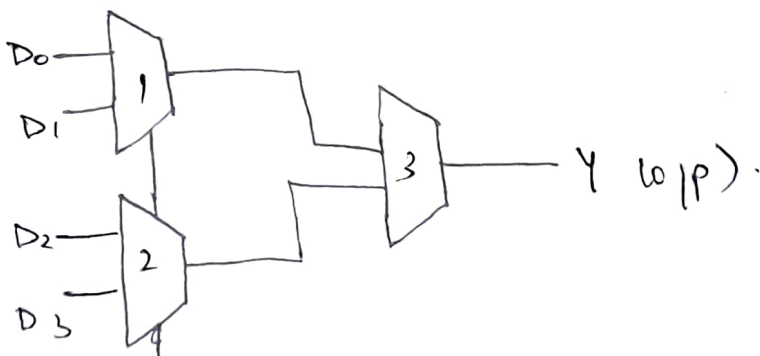
→  $S_1 = 0$

→ when  $S_0 = 00$ , the i/p  $D_0$  is directed as output.

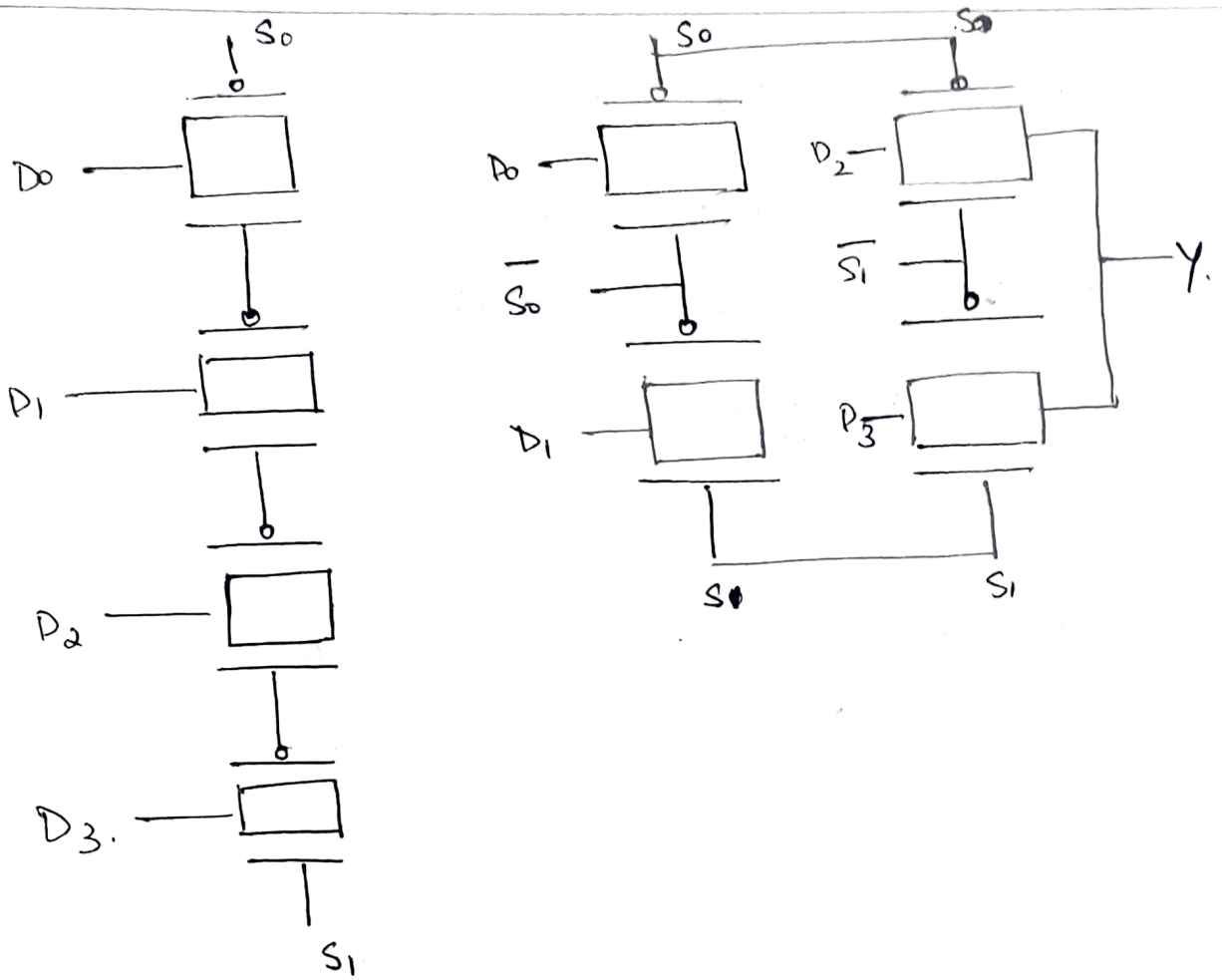
→ when  $S_0 = 01$ , the i/p  $D_1$  is selected and directed as o/p

→ when  $S_0 = 10$ , the i/p  $D_2$  is selected and directed as o/p

→ when  $S_0 = 11$ , the i/p  $D_3$  is selected and directed as o/p

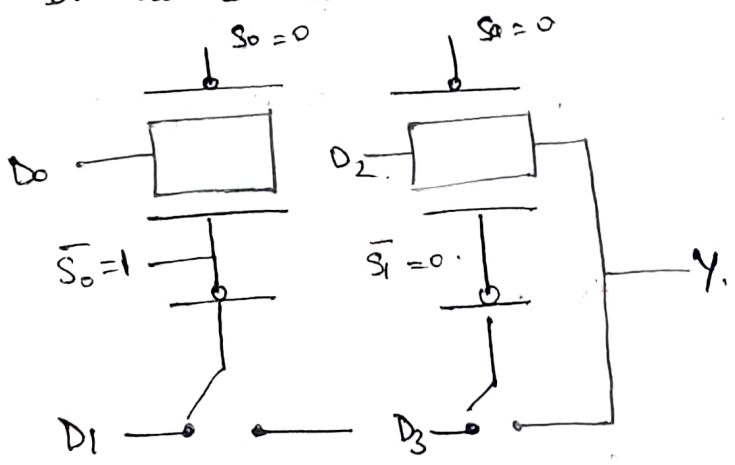






When  $S_0 = 0 + S_1 = 0$ .

i/p  $D_0$  is selected and directed to opp.  $Y$ .



when  $S_0 = 0 + S_1 = 1$ , i/p  $D_1$  is selected and directed to the output  $Y$ .

